

Via Express Mail Label #EL540189538US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: TSUTOMU YAMADA, ET AL.

FOR: DEPOSITION MASK AND MANUFACTURING METHOD THEREOF, AND
ELECTROLUMINESCENCE DISPLAY DEVICE AND MANUFACTURING
METHOD THEREOF

PRELIMINARY AMENDMENT

Box Patent Application
The Assistant Commissioner of
Patents and Trademarks
Washington, DC 02031

Sir:

"Express Mail" mailing label number EL540189538US
Date of Deposit December 26, 2000
I hereby certify that this paper or fee is being deposited
with the United States Postal Service "Express Mail
Post Office to Addressee" service under 37 CFR 1.10
on the date indicated above and is addressed to the
Commissioner of Patents and Trademarks, Washington,
D.C. 20231.
Jennifer Matson
(Typed or printed name of person mailing paper or fee)
Jennifer Matson
(Signature of person mailing paper or fee)

Prior to the Examiner acting in the above-referenced application, please preliminary
amend the abstract and claims as follows:

IN THE ABSTRACT:

Please amend the abstract as follows:

A single crystal or polycrystalline silicon substrate [(100)] is formed as a semiconductor substrate. Using a resist [(103)], an SiO₂ film [(101)] is formed as a first coating on at least part of the outer periphery of the substrate [(100)]. While using this SiO₂ film [(101)] as a mask, the substrate [(100)] is etched from the first surface side using KOH or the like. The thickness of the

substrate is thus decreased to thereby form an opening forming region M, whereas a region of the substrate covered with the first coating is not etched to thereby form a thick portion [140]. Then, on a second surface of the substrate [(100)], a second coating is formed by applying a resist [(104)] at a region of the substrate other than where openings are to be formed in the region M. The substrate is then etched using the second coating as a mask to form holes, as openings [(101)], at regions not covered by the second coating. By using the thus obtained deposition mask [(100)] as a mask for evaporation, a material can be deposited to a desired location with high accuracy.

IN THE CLAIMS:

Claim 1, line 2, delete “including” and insert - -comprising:- -.

Claim 6, line 2, after “mask” insert - -is- -.

Claim 6, line 3, after “performed” insert - -and- -.

Claim 9, line 2, delete “composed by arranging” and insert - -, said device including- -.

REMARKS

Applicant requests entry of the above-identified amendments which conform the claims to U.S. practice. No new matter is being introduced by this Amendment as antecedent support is set forth in the specification and the original claims.

Prosecution on the merits is respectfully requested.

If there are any charges with respect to this Amendment or otherwise, please charge them to Deposit Account No. 06-1130 maintained by Applicants' attorneys.

Respectfully submitted,

TSUTOMU YAMADA, ET AL.

CANTOR COLBURN LLP

Applicants' Attorney

By: 

Daniel F. Drexler

Registration No. P47,535

Customer No. 23413

Date: December 26, 2000